Photolithography: CD vs dose
Contact CD

Contact CD Vs Exposure Dose Mj/cm² IX405 i-line
Photoresist Nominal 0.80u

\[ y = 0.0013x + 0.5853 \]

\[ R^2 = 0.927 \]

ASML 5500/100C Exposure dose mj/cm²
Photolithography: CD vs focus
Contact CD

![Graph showing CD vs focus for contact CD.

- **Graph Title:** GST 40: CONTACT DOF
- **Subtitle:** DI & FI CD (1.17KA IX405)

- **Axes:**
  - X-axis: ASM 5500/100D Focus microns
  - Y-axis: Contact CD microns

- **Legend:**
  - 201CE N D I 200
  - 201CE N FI 200
  - 201 UP DI 200
  - 201 UP FI 200
  - 201 BOT DI 200
  - 201 BOT FI 200

- **Data Points:**
  - Various data points are plotted on the graph, indicating the relationship between focus and contact CD for different conditions.

Steve Brainerd Photo Class
Photolithography: CD vs Dose Linewidth CD

Polysilicon Linewidth DUV photoresist
0 Focus offset.

\[ y = -0.0267x + 1.0649 \]

\[ R^2 = 0.9727 \]